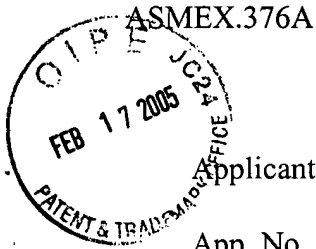


IFW
PATENT



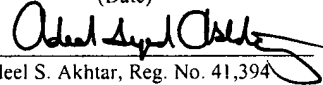
ASMEX.376A
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Todd et al.
App. No. : 10/623,482
Filed : July 18, 2003
For : METHOD TO FORM ULTRA
HIGH QUALITY SILICON-
CONTAINING COMPOUND
LAYERS
Examiner : Unknown
Group Art Unit: 2812

I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

February 14, 2005

(Date)



Adeel S. Akhtar, Reg. No. 41,394

STATUS LETTER

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

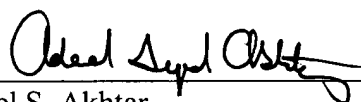
Our file for the subject application reveals that there has been no action in this application since it was filed, i.e., July 18, 2003.

Please inform us as to the status of this application.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: February 14, 2005

By: 
Adeel S. Akhtar
Registration No. asa#
Attorney of Record
Customer No. 20,995
(415) 954-4114